



1. Title:	Plasma cleaning of multilayer coatings from carbon and tin contaminations
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3. Abstract body:

This paper deals with the possibility of total cleaning of EUV reflecting coatings from the thin nm-thickness layers of carbon and tin by using the low-pressure rf plasma. The Mo:Si samples with few-nm layers of tin and carbon were cleaned both in the discharge afterglow due to purely reactive radical etching and in plasma itself where etching is moreover enhanced by soft energetic ions incident on a surface. The experiments have demonstrated principal possibility to find such plasma condition that provide practically total cleaning of multilayer coatings without any noticeable defects.